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Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Complete if Known			
		Application Number	To be assigned		
		Filing Date	October 16, 2003		
		First Named Inventor	Sang-In Han		
		Group Art Unit	Unknown		
Examiner Name	Unknown				
Sheet	2	of	2	Attorney Docket Number	001.3000

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
AC		H.L. CHEN and L.A. WANG, "Simulation on a New Reflection Type Attenuated Phase Shifting Mask for Extreme Ultraviolet Lithography", Institute of Electro-Optical Engineering National Taiwan University, Taipei, Taiwan, R.O.C.; Part of the SPIE Conference on Emerging Lithographic Technologies III, Santa Clara, California, March 1999, SPIE Vol. 3676, 0277-786X/99.	
SC		PAWITTER MANGAT, SCOTT HECTOR, STEWART ROSE, GREG CARDINALE, EDITA TEJNIL, ALAN STIVERS, "EUV Mask Fabrication With Cr Absorber", Motorola, Inc., Advanced Products Research and Development Laboratory, Austin TX, Sandia National Laboratories, Livermore, CA, Intel Corporation, Santa Clara, CA; In Emerging Lithographic Technologies IV, Elizabeth A. Dobisz, Editor, Proceedings of SPIE Vol. 3997 (2000), 0277-786X/00.	
SC		STEPHEN P. VERNON, PATRICK A. KEARNEY, WILLIAM M. TONG, SHON PRISBREY, CINDY LARSON, CRAIG E. MOORE, FRANK W. WEBER, GREG CARDINALE, PEI-YANG YAN, SCOTT D. HECTOR, "Masks for Extreme Ultraviolet Lithography", Lawrence Livermore National Laboratory, Livermore, CA, Sandia National Laboratories, Livermore, CA, Intel Corporation, Santa Clara, CA, Motorola, Inc., Austin, TX; Part of the BACUS Symposium on Photomask Technology and Management, Redwood City, CA, September 1998, SPIE Vol. 3546, 0277-786X/98.	

Examiner Signature	<i>A. Rosasco</i>	Date Considered	5-23-05
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation, if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² Applicant is to place a check mark here if English Language Translation is attached.

